Microlithography NA TC Chapter
Meeting Summary and Minutes
SEMICON West
Tuesday, July 12, 2016, 2:00 PM - 3:00 PM
San Francisco Marriott Marquis, San Francisco, California

TC Chapter Announcements

Next TC Chapter Meeting
Tentatively scheduled during November 7-10, 2016 San Jose, CA in conjunction with the NA Fall Standards Meeting 2016. Check www.semi.org/standards for the latest update.

Table 1 Meeting Attendees
Co-Chairs: Bryan Barnes (NIST)
SEMI Staff: Kevin Nguyen (SEMI HQ)

<table>
<thead>
<tr>
<th>Company</th>
<th>Last</th>
<th>First</th>
</tr>
</thead>
<tbody>
<tr>
<td>NIST</td>
<td>Barnes</td>
<td>Bryan</td>
</tr>
<tr>
<td>Xyalis</td>
<td>Hurat</td>
<td>Sylvie</td>
</tr>
</tbody>
</table>

Table 2 Task Force or Leadership Changes
None

Table 2 Ballot Results
None

Table 3 Authorized Activities

<table>
<thead>
<tr>
<th>#</th>
<th>Type</th>
<th>SC/TF/WG</th>
<th>Details</th>
</tr>
</thead>
<tbody>
<tr>
<td>6040</td>
<td>SNARF</td>
<td>Data Path TF</td>
<td>Line Item Revision to SEMI P44-0316 Specification for Open Artwork System Interchange Standard (OASIS ®) Specific to Mask Tools</td>
</tr>
</tbody>
</table>

NOTE 1: SNARFs and TFOFs are available for review on the SEMI Web site at: http://downloads.semi.org/web/wstdsbal.nsf/TFOFSNARF

Table 4 Authorized Ballots

<table>
<thead>
<tr>
<th>#</th>
<th>When</th>
<th>SC/TF/WG</th>
<th>Details</th>
</tr>
</thead>
<tbody>
<tr>
<td>6040</td>
<td>TBD</td>
<td>Data Path TF</td>
<td>Informational Ballot - Line Item Revision to SEMI P44-0316 Specification for Open Artwork System Interchange Standard (OASIS ®) Specific to Mask Tools</td>
</tr>
</tbody>
</table>

Table 5 New Action Items
None

Table 6 Previous Meeting Action Items
None
1 Welcome, Reminders, and Introductions

Bryan Barnes called the meeting to order at 2:00 PM. The meeting reminders on antitrust issues, intellectual property issues and holding meetings with international attendance were reviewed. Attendees introduced themselves.

2 Review of Previous Meeting Minutes

The TC Chapter reviewed the minutes of the previous meeting.

Motion: Accept the minutes as written
By / 2nd: Bryan Barnes/Sylvie Hurat
Discussion: None
Vote: 2-0

3 Liaison Report

3.1 Micropatterning Japan TC Chapter

Kevin Nguyen reported for the Japan TC Chapter. Of Note:

- Disbandment of Japan Chapter of Global Micropatterning was agreed upon at the TC Chapter meeting on May 20, 2016.
  - It will be reported at the next JRSC meeting on August 26.
- Although Japan Chapter is disbanded, they continue to support Standards activities as a TC member of Global Micropatterning Technical Committee!!

Attachment: 01, 2016.07.12 Micropatterning Japan_N_R0.1

3.2 SEMI Staff Report

Kevin Nguyen (SEMI) gave the SEMI Staff Report. Of note:

- Next meetings
  - November 7-10, 2016
    - SEMI HQ in San Jose, California
  - April 3-6, 2017
    - SEMI HQ in San Jose, California
  - July 10-13, 2017
    - San Francisco, California
- 2016 Critical Dates for SEMI Standards Ballots
  - Cycle 6
    - Ballot submission deadline: July 22
    - Voting opens: August 1
    - Voting closes: Sept 1
  - Cycle 7
    - Ballot submission deadline: Aug 17
    - Voting opens: August 31
    - Voting closes: Sept 30
- 5 Year Review
4 Ballot Review

None

5 Subcommittee and Task Force Reports

5.1 Data Path Task Force

No report

5.2 Extreme Ultraviolet (EUV) Fiducial Mark Task Force

No report

5.3 Extreme Ultraviolet (EUV) Mask Task Force

No report

6 Old Business

None

7 New Business

- P44 SNARF
  - Kevin Nguyen presented a SNARF for Line Item Revision to SEMI P44-0316 Specification for Open Artwork System Interchange Standard (OASIS®) Specific to Mask Tools, on Thomas Grebinski’s behalf.

Motion: Approve P44 Line Item SNARF

By / 2nd: Bryan Barnes/Sylvie Hurat

Discussion: None

Vote: 2-0

Attachment: 03, SNARF_P44_64_bit_coordinate_space_proposal rev1
• P44 Informational Ballot
  o As requested by Thomas Grebinski, Kevin Nguyen showed the ballot for Line Item Revision to SEMI P44-0316 Specification for Open Artwork System Interchange Standard (OASIS ®) Specific to Mask Tools.

Motion: To issue P44 line-item revision for Informational Ballot
By / 2nd: Bryan Barnes/Sylvie Hurat
Discussion: None
Vote: 2-0

8 Next Meeting and Adjournment
The next meeting is scheduled for Tuesday, November 8, 2016 in San Jose, CA in conjunction with NA Fall Standards meetings. See http://www.semi.org/en/events for the current list of meeting schedules.

Having no further business, a motion was made to adjourn. Adjournment was at 2:30 PM.

Respectfully submitted by:
Kevin Nguyen,
SEMI Standards Operations Manager
Phone: 408-943-7997
Email: knguyen@semi.org

Minutes approved by:
Bryan Barnes (NIST) August 16, 2016
<Name> (<Company>), Co-chair <Date approved>

Table 7 Index of Available Attachments#1

<table>
<thead>
<tr>
<th>Title</th>
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</thead>
<tbody>
<tr>
<td>2016.07.12 Micropatterning Japan_N_R0.1</td>
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<tr>
<td>Staff Report June 2016 Micro</td>
<td></td>
</tr>
<tr>
<td>SNARF_P44_64_bit_coordinate_space_proposal</td>
<td></td>
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#1 Due to file size and delivery issues, attachments must be downloaded separately. A .zip file containing all attachments for these minutes is available at www.semi.org. For additional information or to obtain individual attachments, please contact [SEMI Staff Name] at the contact information above.